

Intrepid Atlas Photoresist Stripper

The Atlas Automated Photoresist Stripper is a vacuum loadlocked, high throughput, multi-chamber, resist stripping system that supplies up to 250 wafers per hour on 300 mm wafers. It has an extremely low particle transport, which automatically loads 4 wafers at a time into two separate vacuum transfer chambers. Thus, the system continuously runs without venting each wafer to atmosphere. Therefore the maximum possible throughput and the lowest possible particle count are achieved.



Process Chamber

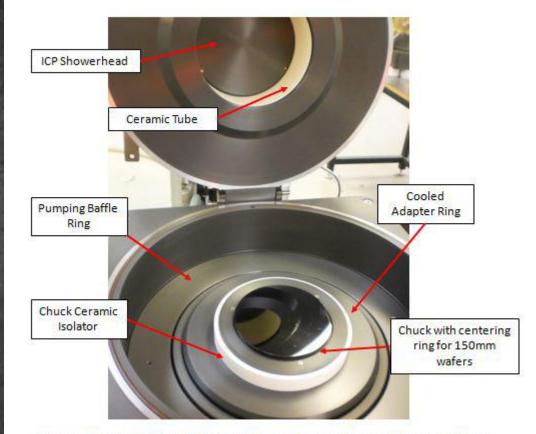
Proprietary Plasma Reactor

This system incorporates three low damage plasma reactors, which provide strip rates up to 10 microns per minute each.

Intrepid provides three technologies for resist stripping:

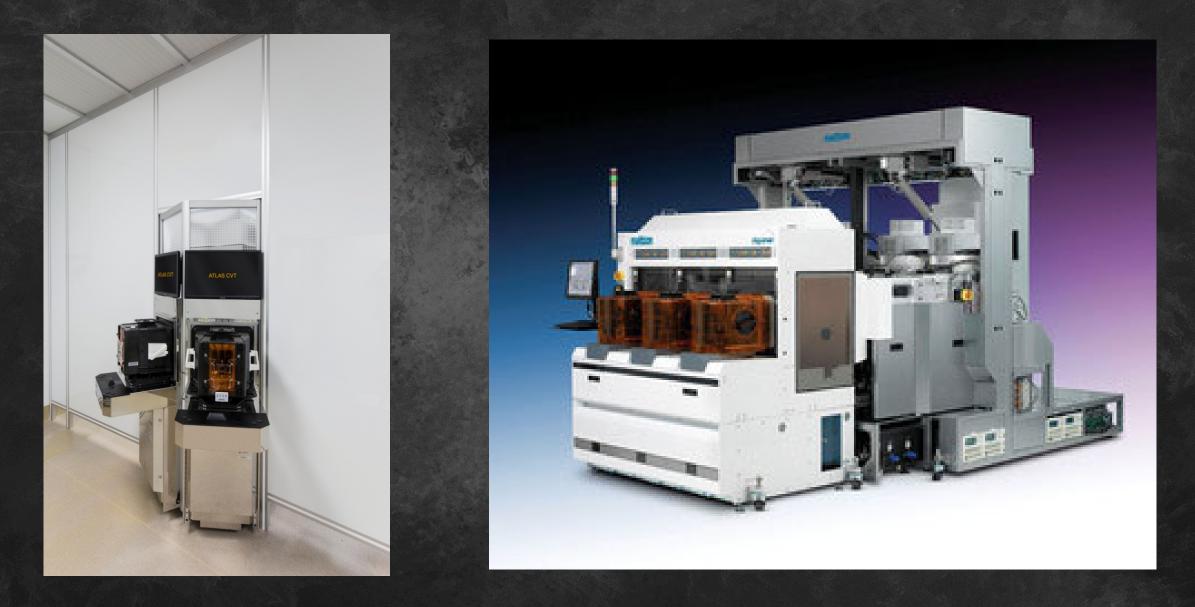
- 1. Proprietary Reactor (patent pending)
- 2. Microwave
- 3. ICP

ICP & Chamber Assembly

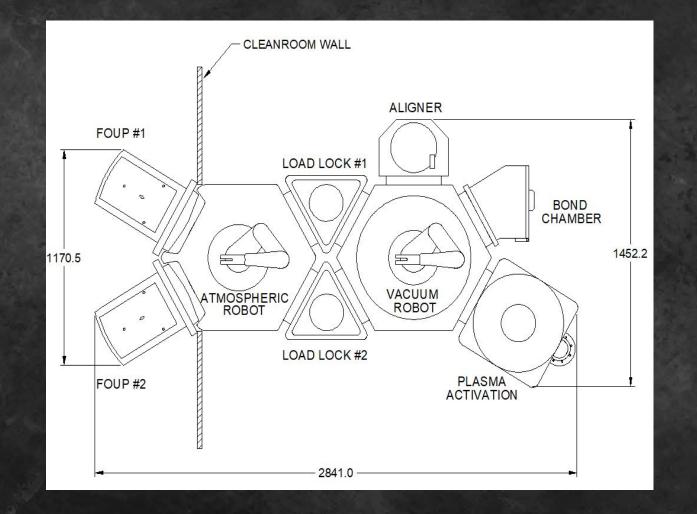


Picture shows 150mm wafer in the lifted position, awaiting pickup

System Footprint: Intrepid vs Mattson



System Layout



~ Please ask about our new Hydrogen Strip System ~

Contact Us

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